

Form PTO 1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. MI22-1898		SERIAL NO. 10/050,348	
<div style="display: flex; align-items: center; justify-content: center;"> <div style="border: 2px solid black; border-radius: 50%; padding: 10px; text-align: center; margin-right: 10px;"> OTPE NOV 04 2002 PATENT & TRADEMARK OFFICE </div> <div> LIST OF ART CITED BY APPLICANT (Use several sheets if necessary) </div> </div>					APPLICANT Gurtej S. Sandhu et al.			GROUP 2813
					FILING DATE January 15, 2002			

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U.S. PATENT DOCUMENTS							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA	5,032,545	07/91	Doan et al.			
	AB	5,436,481	07/95	Egawa et al.			
	AC	5,378,645	01/95	Inoue et al.			
	AD	5,258,333	11/93	Shappir et al.			
	AE	5,518,946	05/96	Kuroda			
	AF	5,445,999	08/95	Thakur et al.			
	AG	5,382,533	01/95	Ahmad et al.			
	AH	5,663,077	09/97	Adachi et al.			
	AI	5,026,574	06/91	Economu et al.			
	AJ	5,026,574	06/91	Economu et al.			
	AK	5,612,558	11/95	Harshfield			
	AL	5,719,083	06/95	Komatsu			

FOREIGN PATENT DOCUMENTS							
	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
	AM	WO 96/39713	12/96	PCT			
	AN						
	AO						
	AP						
	AQ						

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)			
	AR		Wolf, S., "Silicon Processing for the VLSI Era", Lattice Press 1990, Vol. 2, pp. 212-213.
	AS		Wolf, S., "Silicon Processing for the VLSI Era", Lattice Press 1990, Vol. 2, pp. 188-189, 194-195, 609-614.
	AT		Ko, L. et al., "The Effect of Nitrogen Incorporation into the Gate Oxide By Using Shallow Implantation of Nitrogen and Drive-In Process", IEEE 1996, pp. 32-35.

EXAMINER	DATE CONSIDERED
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Form PTO-449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. MI22-1898		SERIAL NO. 09/633,556	
<div style="position: relative; height: 100px;"> <div style="position: absolute; top: 0; left: 0; width: 100%; height: 100%; border: 2px solid black; border-radius: 50%; text-align: center; font-size: 24px; line-height: 1;"> U.S. PATENT & TRADEMARK OFFICE NOV 04 2002 </div> </div>					LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)			
					APPLICANT Gurtej S. Sandhu et al.			
					FILING DATE August 7, 2000		GROUP 2813	

U.S. PATENT DOCUMENTS							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA	5,760,475	06/98	Cronin			
	AB	5,834,372	11/98	Lee			
	AC	5,619,057	04/96	Komatsu			
	AD	5,633,036	05/97	Seebauer et al.			
	AE	6,054,396	04/00	Doan			
	AF	6,174,821	01/01	Doan			
	AG	5,939,750	08/99	Early			
	AH	5,254,489	10/93	Nakata			
	AI	5,464,792	11/95	Tseng et al.			
	AJ	5,620,908	04/97	Inoh et al.			
	AK	5,716,864	02/98	Abe			
	AL	5,972,783	10/99	Arai et al.			

FOREIGN PATENT DOCUMENTS							
Document Number	Date	Country	Class	Subclass	Translation		
					Yes	No	
AM							
AN							
AO							
AP							
AQ							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)			
	AR		Doyle, B. et al., "Simultaneous Growth of Different Thickness Gate Oxides in Silicon CMOS Processing", IEEE Vol. 16 (7), July 1995, pp. 301-302.
	AS		Kuroi, T. et al., "The Effects of Nitrogen Implantation Into P+Poly-Silicon Gate on Gate Oxide Properties", 1994 Sympos. on VLSI Technology Digest of Technical Papers, IEEE 1994, pp. 107-108.
	AT		Liu, C.T. et al., "Multiple Gate Oxide Thickness for 2GHz System-on-a-Chip Technologies", IEEE 1998, pp. 589-592.

EXAMINER	DATE CONSIDERED
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Form PTO-159		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-1898		SERIAL NO. 09/633,556		
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Gurtej S. Sandhu et al.				
				FILING DATE August 7, 2000		GROUP 2813		
U.S. PATENT DOCUMENTS								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
<i>JS</i>	AA	6,091,109	07/00	Hasegawa				
<i>JS</i>	AB	6,080,682	06/00	Ibok				
<i>JS</i>	AC	5,685,949	11/97	Yashima				
<i>JS</i>	AD	6,268,296 B1	07/01	Misium et al.				
<i>JS</i>	AE	6,232,244 B1	05/01	Ibok				
<i>JS</i>	AF	6,331,492	12-2001	Misium et al.				
<i>JS</i>	AG	6,080,629	06-2000	Gardner et al.				
<i>JS</i>	AH	5,970,345	10-1999	Hattangady et al.				
<i>JS</i>	AI	5,885,877	03-1999	Gardner et al.				
<i>JS</i>	AJ	6,323,114 B1	11-2001	Hattangady et al.				
<i>JS</i>	AK	6,184,110 B1	02-2001	Ono et al.				
	AL							
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AM							
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	AO							
	AP							
	AQ							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
	AR							
	AS							
	AT							
EXAMINER <i>James Schultz</i>				DATE CONSIDERED <i>3/1/03</i>				
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